

ABSTRACT OF THE DISCLOSURE

A slot antenna plate is placed on a second dielectric for radiating microwave into a chamber interior, the slot antenna plate being provided on a side of the second dielectric that faces the chamber interior. The slot
5 antenna plate is made of conductor and includes slots for passing the microwave therethrough to the chamber interior. In this way, a plasma processing apparatus is provided generating plasma by microwave, the plasma processing apparatus capable of easily adjusting ion irradiation energy for a material to be processed to achieve uniform plasma processing
10 for the material within the plane of the material.